

Title (en)

Electrolytic bath for the deposition of thin layers of pure gold.

Title (de)

Elektrolytisches Bad für das Abscheiden dünner Schichten reinen Goldes.

Title (fr)

Bain électrolytique pour le dépôt de couches minces d'or pur.

Publication

EP 0149830 A2 19850731 (FR)

Application

EP 84115879 A 19841220

Priority

CH 696183 A 19831229

Abstract (en)

1. Electrolytic bath for the deposit of thin layers of pure gold on passive surfaces, containing from 0.5 to 20 g/l of gold under the form of a gold cyanide of alkali metal, in which gold is trivalent, and at least an acid which is present in a sufficient concentration so as the pH of this bath is at most of 0.4, characterized in that the acid is selected from the group comprising the sulfuric acid, the sulfamic acid, the pyrophosphoric acid, the mono-, di- and tri-chloroacetic acids, the malic acid, and the 1-hydroxy-1, 1-ethylidene-diphosphonic, hydroxy-methylphosphonic and amino-tris(methylene-phosphonic) acids, and the mixtures thereof.

Abstract (fr)

Le bain électrolytique, permettant de déposer des couches minces (environ 0, 5 µ) d'or pur sur des surfaces passives, contient de 0,5 à 20 g/l d'or sous forme d'auricyanure de K ou Na, ainsi qu'un acide ou un mélange d'acides en une quantité telle que le pH du bain soit d'au plus 0,4, et de préférence entre 0,1 et 0,3.

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